

M.Tech. VLSI Design and Microelectronics Technology, 2024
Second Year First Semester

QUANTUM AND NANOELECTRONIC DEVICES

Time: 3 Hours

Full Marks: 100

Answer any FIVE Questions.

- Q1.a) Describe features of three different types of band edge line-ups that may occur at a Heterojunction. Also mention one example of each category. 8
- b) With adequate band diagram, show that in above cases band gap offset (ΔE_g) is either the sum or the difference of conduction band discontinuity (ΔE_c) and valence band discontinuity (ΔE_v). 6
- c) Describe a scheme for the experimental determination of the value of $Q (= \Delta E_c / \Delta E_g)$. Use a parabolic quantum well for that. 6
- Q2.a) Describe Poisson effect in context with the pseudomorphic growth of an epitaxial layer over an appropriate semiconductor substrate. 8
- b) Verify whether pseudomorphic growth of SiGe alloy on Si substrate is feasible or not. If possible, determine the critical thickness (d_c) of the $\text{Si}_{1-x}\text{Ge}_x$ layer for $x = 0, 0.1, 0.3, 0.5, 0.7, 1$; and form the boundary between regions for Pseudomorphic and Metamorphic growths. Take lattice constants for Si and Ge as 5.43 \AA and 5.65 \AA respectively. 2+8+2
- Q3.a) Formulate the time-independent Schrodinger equation from the general time-dependent Schrodinger equation. 6
- b) Elaborate an appropriate scheme for determination of the following: 8+6
- (i) Energies of an electron confined in a well with finite barrier,
 - (ii) Transmission co-efficient of an electron through a double-barrier system.
- Consider appropriate structures and make necessary assumptions for each case.
- Q4.a) Write (**no derivation**) the general form of DOS function for bulk semiconductor. Next, determine the (i) DOS function and (ii) Carrier 1+7+6

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concentration for a long semiconductor wire of rectangular cross-section $d_y d_z$, where both d_y and d_z are comparable to the electron wavelength. Assume the $E - k$ dispersion relation for the semiconductor to be parabolic.

- b) Sketch variations in *DOS functions* with *Energy* for Bulk, QW, QWW and QD in a single figure. 6
- Q5.a) Discuss a model that helps in determining the ordering of atoms A and B in alloy $A_x B_{1-x}$. 6
- b) Explain how the Heavy hole (HH) and Light hole (LH) bands originate. 6
- c) What is Landau quantization and what are the conditions favorable to such quantization? Describe the changes in electron distribution under its influence. 4+4
- Q6.a) Explain *Resonant Tunneling*. Describe the J - V characteristics of a Resonant tunneling diode (RTD) with appropriate energy band diagrams. 4+8
- b) Determine the no. of *NDR* regions expected in an RTD comprising of a 30 nm *GaAs* QW sandwiched between $Al_{0.3}Ga_{0.7}As$ barriers. 8
Given that: for *AlAs* $E_g = 2.16$ eV, for *GaAs* $E_g = 1.42$ eV and $m_n^* = 0.067 m_0$, m_0 being the free electron mass, $Q (= \Delta E_c / \Delta E_g) = 0.62$ at above heterojunctions.
- Q7. Differentiate: 6+8+6
- Maxwell – Boltzmann distribution and Fermi – Dirac distribution,
 - Compositionally graded superlattice and n - i - p - i superlattice,
 - Acoustic phonon and Optic phonon.
- Q8. Write notes on **any TWO**: 2x10
- Real Space Transfer of electrons,
 - Quantum Hall Effect,
 - SEED as an optical switch,
 - Single Electron Transistor.